

**X-RAY MEASURING APPARATUS AND METHOD**

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**Abstract**

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**PROBLEM TO BE SOLVED:** To enable the measurement of a sample over a range from the minute region of the sample to the wide region thereof by one X-ray optical system in a case performing measurement, by adjusting the X-ray irradiation field to the sample by using a collimator or the like, and to obtain data of high dissolving power in relation to the whole range from the minute region to the wide region.

**SOLUTION:** A sample S is irradiated with X-rays in a narrow X-ray irradiation field A by a collimator 1 and X-rays diffracted by the sample S are detected by a storage phosphor 2. When the measuring region B of the sample S is wider than the X-ray irradiation region by the collimator 1, the sample S is moved in parallel to the collimator 1 by an XY parallel moving device 6 to scan and move the X-ray irradiation field A to regulate the measuring region B. Diffracted X-ray data are successively integrated on the stimuable phosphor 2 when the X-ray irradiation field is present at the individual positions in the measuring region B.

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